

JUL 30 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**OFFICIAL**

Applicant(s): Chiang, Tony P.; Leeser, Karl F.

Assignee: Novellus Systems, Inc. (reassigned)

Title: Method for Integrated In-Situ Cleaning and Subsequent Atomic Layer Deposition Within a Single Processing Chamber

Serial No.: 09/994,279

Filing Date: November 26, 2001

Examiner: David Nhu

Group Art Unit: 2818

Docket No.: PA1688 US

San Jose, California  
July 30, 2004Mail Stop Petition  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450RESPONSE TO FINAL OFFICE ACTION01/31/2005 GSTANLEY 000002 502886 03-04-07  
01 FC:1201 86 00 DA  
Dear Sir:

This responds to the Office Action dated February 5, 2003, in the above-identified application. The application was unintentionally abandoned, and the appropriate petition for revival is enclosed herewith. Please amend the application to place all claims in condition for allowance as follows.

Amendments to the claims begin on page 2.

Amendments to the specification begin on page 7.

Remarks begin on page 8.

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